

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
SHABANI et al.

Serial No.: 09/775,209

Filed: February 1, 2001

Art Unit: 2877

Examiner: T.T. Nguyen

Attorney Docket No.: JG-SU-5038/500577.20021

**METHOD FOR ANALYZING
IMPURITIES IN A SILICON
SUBSTRATE AND
APPARATUS FOR
DECOMPOSING A SILICON
SUBSTRATE THROUGH
VAPOR-PHASE REACTION**

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

CUSTOMER NO. 026418

AMENDMENT AND RESPONSE TO OFFICE ACTION

Dear Sir:

In response to the Office Action mailed August 20, 2003, it is respectfully requested that the following amendments be entered and the accompanying remarks be considered. The three (3) month shortened statutory period for response is set to expire on November 20, 2003. Therefore, this response is being timely filed.

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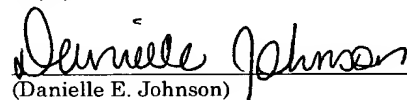
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(Danielle E. Johnson)

(Signature of person mailing paper or fee)